



Future Normal in Semiconductor

2025년 2월 13일(목), 10:55-12:40

Room L(하트II+III), 6층

B. Patterning (Lithography & Etch Technology) 분과

O24_[TL2-B] Lithography

좌장: 이진균 교수(인하대학교), 김지호 선임연구원(포항공과대학교 포항가속기연구소)

<p>초청 TL2-B-1 10:55-11:25</p>	<p>Challenges and Development Status of Next Generation EUV Patterning Materials Chawon Koh Yonsei University</p>
<p>TL2-B-2 11:25-11:40</p>	<p>Memory Device의 High NA EUV Stitching 고려사항 Dae-Jin Park, Da-Jeong Kang, Jeon-Kyu Lee, and Sung-Woo Ko SK Hynix Inc.</p>
<p>초청 TL2-B-3 11:40-12:10</p>	<p>Enhancing the Patterning Performance of Metal Oxide Resists for High NA EUV Lithography Yejin Ku¹, Gayoung Kim¹, Jin-Kyun Lee¹, Jiho Kim², Sangsul Lee², Seohyeon Lee³, Byung Jun Jung³, Chawon Koh⁴, Tsunehiro Nishi⁵, and Hyun-Woo Kim⁵ ¹Inha University, ²Pohang Accelerator Laboratory, ³Korea University of Seoul, ⁴Yonsei University, ⁵Samsung Electronics Co., Ltd.</p>
<p>TL2-B-4 12:10-12:25</p>	<p>IM-HAPPY: AI-Based Polymer Resist Design for Enhanced Patterning Performance Jihun Ahn¹, Hyunseok Kim¹, Vikram Thapar¹, Gabriella Pasya Irianti¹, and Su-Mi Hur^{1,2} ¹Department of Polymer Engineering, Graduate School, Chonnam National University, ²School of Polymer Science and Engineering, Chonnam National University</p>
<p>TL2-B-5 12:25-12:40</p>	<p>High-NA EUV 마스크 적용을 위한 차세대 흡수 소재 패터닝 성능 개선 연구 김연수^{1,2}, 정동민^{1,2}, 이승호^{1,2}, 이태호², 안진호^{1,2} ¹한양대학교 신소재공학과, ²Center for Hyperscale, Hyperfunction, Heterogeneous Integration Pioneering Semiconductor Technology</p>